

# ABSTRACT OF THE DISCLOSURE

An exposure apparatus includes a plurality of purge spaces delimited along the optical path between the laser light source and the substrate by housings the  
5 boundary members of which are invisible to the exposing light, and pressure regulating unit for exercising control in such a manner that the pressure within each purge space attains a predetermined value. In the exposure apparatus that is purged in sections,  
10 therefore, it is possible to reduce the amount of deformation of the end faces between mutually adjacent purge spaces, e.g., the end face of a projection optics unit.